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Substitute for form 1449/PTO  <h2 style="text-align: center;">INFORMATION DISCLOSURE STATEMENT BY APPLICANT</h2> <p style="text-align: center;">(Use as many sheets as necessary)</p>		<h3 style="text-align: center;">Complete if Known</h3> <table border="1" style="width: 100%; border-collapse: collapse;"> <tr> <td style="width: 50%;">Application Number</td> <td>Not yet assigned</td> </tr> <tr> <td>Filing Date</td> <td>Herewith</td> </tr> <tr> <td>First Named Inventor</td> <td>James S. Im</td> </tr> <tr> <td>Art Unit</td> <td>Not yet assigned 2823</td> </tr> <tr> <td>Examiner Name</td> <td>Not yet assigned W. David Coleman</td> </tr> <tr> <td>Attorney Docket Number</td> <td>A35185-PCT-USA (070050.2727)</td> </tr> </table>		Application Number	Not yet assigned	Filing Date	Herewith	First Named Inventor	James S. Im	Art Unit	Not yet assigned 2823	Examiner Name	Not yet assigned W. David Coleman	Attorney Docket Number	A35185-PCT-USA (070050.2727)
Application Number	Not yet assigned														
Filing Date	Herewith														
First Named Inventor	James S. Im														
Art Unit	Not yet assigned 2823														
Examiner Name	Not yet assigned W. David Coleman														
Attorney Docket Number	A35185-PCT-USA (070050.2727)														
Sheet 1	of 1														

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)			
W.C./	1	US- 4691983	09-08-1987	Kobayashi et al.	
W.C./	2	US- 5304357	04-19-1994	Sato et al.	
W.C./	3	US- 5591668	01-07-1997	Maegawa et al.	
W.C./	4	US- 6368945	04-09-2002	James S. Im	
W.C./	5	US- 2001/0041,426	11-15-2001	James S. Im	
W.C./	6	US- 6322625	11-27-2001	James S. Im	
W.C./	7	US- 6573531	06-03-2003	Im et al.	
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FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages Or Relevant Figures Appear	T <sup>6</sup>
		Country Code <sup>3</sup> Number <sup>4</sup> Kind Code <sup>5</sup> (if known)				

Examiner Signature	 Digitally signed by W. David Coleman DN: cn=W. David Coleman, c=US, o=USPTO, ou=2823, email=William.Coleman@uspto.gov Reason: I have reviewed this document Date: 2007.07.10 12:42:08 -04'00'	Date Considered	07/10/2007
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	Applicant James S. Im	
	Filing Date 02/16/2005	Group <del>TBD</del> 2823
	Examiner Not yet assigned	W. David Coleman

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W.C./	3	4309225	01/05/1982	Fan et al.
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NY02:530588.1  Examiner	 <small>           Digitally signed by W. David Coleman            DN: cn=W. David Coleman, ou=USPTO, ou=2823, email=William.Coleman@uspto.gov            Reason: I have reviewed this document            Date: 2007.07.10 11:48:23 -04'00'         </small>	Date Considered  07/10/2007
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W.C./	16	4977104	12/11/1990	Sawada et al.
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Exam. Initial.	No.	Document No.	Issue/Publication Date	Applicant(s)
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	Examiner Not yet assigned	W. David Coleman

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Exam. Initial.	No.	Document No.	Issue/Publication Date	Applicant(s)
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	Applicant James S. Im	
	Filing Date 02/16/2005	Group <del>TDD</del> 2823
	Examiner Not yet assigned	W. David Coleman

Exam. Initial.	No.	Document No.	Issue/Publication Date	Applicant(s)
W.C./	81	6621044	09/01/2003	Jain et al.
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W.C./	128	2005034653	02/17/2005	Im et al.
W.C./	129	6563077	05/13/2003	Im

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Exam. Initial.	No.	Document No.	Issue/Publication Date	Applicant(s)
W.C.	130	6582827	06/24/2003	Im
W.C.	33	6830993	12/14/2004	Im et al.



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Exam Initial	No.	Document No.	Publication Date	Country	Translation	
					Yes	No
W.C./	90	681316	08/11/1995	EP		
W.C./	91	1067593	10/01/2001	EP		
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	97	6252048	09/09/1994	JP		No
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W.C./	103	62181419	08/08/1987	JP		
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	<b>Examiner</b> Not yet assigned	<b>W. David Coleman</b>

Exam Initial	No.	Document No.	Publication Date	Country	Translation	
					Yes	No
W.C./	105	9931719	06/24/1999	WO		No
W.C./	106	0014784	03/16/2000	WO		
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W.C./	121	04017380	02/26/2004	WO		
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	<b>Examiner</b> Not yet assigned	<b>W. David Coleman</b>

Exam Initial	No.	OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.)
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<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (Use several sheets if necessary)	Applicant James S. Im	
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